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# A B S T R A C T

## CRYSTALLIZATION APPARATUS, CRYSTALLIZATION METHOD, AND PHASE SHIFT MASK

A phase shift mask (5) is arranged before a laser device (1) through a beam expander (2), a homogenizer (3) and a mirror (4), and a processed substrate (7) is set on an opposed surface of the phase shift mask (5) with an image forming optical system (6) therebetween. The processed substrate (7) is held at a predetermined position by using a substrate chuck (8) such as a vacuum chuck or an electrostatic chuck.

Fig. 1